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Front Matter: Volume 9173

, "Front Matter: Volume 9173," Proc. SPIE 9173, Instrumentation, Metrology, and Standards for Nanomanufacturing, Optics, and Semiconductors VIII, 917301 (9 September 2014); doi: 10.1117/12.2081270

SPIE.

Event: SPIE NanoScience + Engineering, 2014, San Diego, California, United States

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Instrumentation, Metrology, and Standards for Nanomanufacturing, Optics, and Semiconductors VIII

**Michael T. Postek
Ndubuisi G. Orji**
Editors

**20 August 2014
San Diego, California, United States**

Sponsored and Published by
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Volume 9173

Proceedings of SPIE 0277-786X, V. 9173

SPIE is an international society advancing an interdisciplinary approach to the science and application of light.

Instrumentation, Metrology, and Standards for Nanomanufacturing, Optics, and Semiconductors VIII,
edited by Michael T. Postek, Ndubuisi G. Orji, Proc. of SPIE Vol. 9173, 917301 · © 2014 SPIE
CCC code: 0277-786X/14/\$18 · doi: 10.1117/12.2081270

Proc. of SPIE Vol. 9173 917301-1

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Author(s), "Title of Paper," in *Instrumentation, Metrology, and Standards for Nanomanufacturing, Optics, and Semiconductors VIII*, edited by Michael T. Postek, Ndubuisi G. Orji, Proceedings of SPIE Vol. 9173 (SPIE, Bellingham, WA, 2014) Article CID Number.

ISSN: 0277-786X

ISBN: 9781628412000

Published by

SPIE

P.O. Box 10, Bellingham, Washington 98227-0010 USA

Telephone +1 360 676 3290 (Pacific Time) · Fax +1 360 647 1445

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